Title: IMAGING FOR A MACHINE-VISION SYSTEM

IN THE CLAIMS

Please amend the claims as follows:

1-289. (Cancelled)

290-293. (Cancelled)

294. (Currently Amended) The machine-vision head-according to claim 293,

A machine-vision head for measuring a three-dimensional geometry of a device having a surface to be measured, comprising:

a projector, the projector including:

a first light source having a projection optical axis that intersects the device; a projection-imaging element positioned along the projection optical axis and spaced from the first light source; and

a projection-pattern element positioned between the first light source and the projection imaging element along the projection optical axis, the projection-pattern element having a repeating sine-wave light-modulation pattern as measured along a line on the projection-pattern element; and

an imager, the imager having a reception optical axis that intersects the device substantially at the projection optical axis, wherein the projection-pattern element light-modulation pattern includes a repeating pattern of grid lines having substantially constant density along lines in a direction parallel to the grid lines and a sine-wave density along lines in a direction perpendicular to the grid lines, wherein the first light source includes a elongated incandescent filament having a dimension along a longitudinal axis substantially longer than a width, wherein the longitudinal axis of the filament is substantially perpendicular to the projection optical axis and substantially parallel to the grid lines of the projection-pattern element; and

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a projection mask having an elongated aperture having a dimension along a length axis substantially longer than a dimension along a width axis perpendicular to the length axis, and wherein the length axis is substantially parallel to the grid lines of the projection-pattern element, wherein the projection mask limits the projected light to less than about three sine-wave cycles of the sine-wave pattern.

The machine vision head according to claim 293, further 295. (Currently Amended) comprising

A machine-vision head for measuring a three-dimensional geometry of a device having a surface to be measured, comprising:

a projector, the projector including:

- a first light source having a projection optical axis that intersects the device; a projection-imaging element positioned along the projection optical axis and spaced from the first light source; and
- a projection-pattern element positioned between the first light source and the projection imaging element along the projection optical axis, the projectionpattern element having a repeating sine-wave light-modulation pattern as measured along a line on the projection-pattern element; and

an imager, the imager having a reception optical axis that intersects the device substantially at the projection optical axis, wherein the projection-pattern element lightmodulation pattern includes a repeating pattern of grid lines having substantially constant density along lines in a direction parallel to the grid lines and a sine-wave density along lines in a direction perpendicular to the grid lines, wherein the first light source includes a elongated incandescent filament having a dimension along a longitudinal axis substantially longer than a width, wherein the longitudinal axis of the filament is substantially perpendicular to the projection optical axis and substantially parallel to the grid lines of the projection-pattern element; and

a projection mask having an elongated aperture having a dimension along a length axis substantially longer than a dimension along a width axis perpendicular to the length axis, and

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wherein the length axis is substantially parallel to the grid lines of the projection-pattern element; and

a projection-mask actuator operable to adjust a position of the projection mask.

The machine-vision head according to claim 290 294, further 296. (Currently Amended) comprising a light-intensity controller, coupled to receive intensity information regarding light output from the first light source, that outputs a control signal based on a measured intensity of light from the first light source.

297. (Previously Presented) The machine-vision head according to claim 296, wherein the control signal is operatively coupled to the first light source to control light output based on the measured light intensity in a feedback manner.

The machine-vision head according to claim 296, 298. (Currently Amended) A machine-vision head for measuring a three-dimensional geometry of a device having a surface to be measured, comprising:

a projector, the projector including:

- a first light source having a projection optical axis that intersects the device; a projection-imaging element positioned along the projection optical axis and spaced from the first light source, and
- a projection-pattern element positioned between the first light source and the projection imaging element along the projection optical axis, the projectionpattern element having a repeating sine-wave light-modulation pattern as measured along a line on the projection-pattern element;

an imager, the imager having a reception optical axis that intersects the device substantially at the projection optical axis; and

a light-intensity controller, coupled to receive intensity information regarding light output from the first light source, that outputs a control signal based on a measured intensity of light from the first light source, wherein the control signal is operatively coupled to the imager to control an amount of light received in an imaging cycle of the imager.

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The machine-vision head according to claim 290 294, further 299. (Currently Amended)

comprising a condensing imaging element positioned between the first light source and the

projection-pattern element along the projection optical axis.

The machine-vision head according to claim 290 294, further 300. (Currently Amended)

comprising a focussing reflector that substantially focusses an image of the first light source

adjacent to the first light source.

301. (Previously Presented) The machine-vision head according to claim 300, wherein the

reception optical axis is oriented to be at substantially a right angle to a direction of scanning,

and the projection optical axis is oriented to be at substantially a forty-five-degree angle to the

direction of scanning.

302. (Previously Presented) The machine-vision head according to claim 301, wherein a major

plane of the projection-imaging element is oriented substantially perpendicular to the projection

optical axis and a major plane of the projection-pattern element is oriented substantially

perpendicular to the projection optical axis.

The machine-vision head according to claim 290 294, further 303. (Currently Amended)

comprising a second light so urce that directs substantially unpatterned light onto the

device, the second light source being activated to allow the imager to obtain two-dimensional

intensity data about the device-from the imager.

304. (Cancelled)

The system according to claim 304 308, wherein the projection-305. (Currently Amended)

pattern element light-modulation pattern includes a repeating pattern of grid lines having

substantially constant density along lines in a direction parallel to the grid lines and a sine-wave

density along lines in a direction perpendicular to the grid lines.

306. (Previously Presented) The system according to claim 305, wherein the first light source includes a elongated incandescent filament having a dimension along a longitudinal axis substantially longer than a width, wherein the longitudinal axis of the filament is substantially perpendicular to the projection optical axis and substantially parallel to the grid lines of the projection-pattern element.

307. (Cancelled)

308. (Currently Amended) The system according to claim 307,

A machine-vision system for inspecting a device, comprising:

an inspection station, the inspection station including:

a projector, the projector including:

a first light source having a projection optical axis that intersects the device;

a projection-imaging element positioned along the projection optical axis and spaced from the first light source; and

a projection-pattern element positioned between the first light source and the projection imaging element along the projection optical axis, the projection-pattern element having a repeating sine-wave light-modulation

pattern as measured along a line on the projection-pattern element; and an imager, the imager having a reception optical axis that intersects the device when the inspection station is in operation, the imager maintained in a substantially fixed relationship to the pattern projector, the imager including at least three lines of semiconductor imaging pixels;

a scanner mechanism that moves the imager relative to the device such that different portions of the device are successively imaged by the imager, wherein the first light source is activated in conjunction with the imager to obtain three-dimensional device geometry data regarding the device;

a comparator coupled to the imager, the comparator comparing one or more characteristics of the acquired three-dimensional device geometry data with an intended predetermined geometry to produce a signal indicative of any device geometry departure of an actual device geometry from the intended predetermined geometry; and

a projection mask having an elongated aperture having a dimension along a length axis substantially longer than a dimension along a width axis perpendicular to the length axis, wherein the length axis is substantially parallel to the grid lines of the projection-pattern element, and

wherein the projection mask limits the projected light to less than about three sine-wave cycles of the sine-wave pattern.

- The system according to claim 304 308, further comprising a light-309. (Currently Amended) intensity controller, coupled to receive intensity information regarding light output from the light source, that outputs a control signal based on a measured intensity of light from the light source, wherein the control signal is operatively coupled to the imager to control an amount of light received in an imaging cycle of the imager.
- The system according to claim 304 308, further comprising a 310. (Currently Amended) focussing reflector that substantially focusses an image of the light source adjacent to the light source.
- The system according to claim 304 308, further comprising a 311. (Currently Amended) condensing imaging element positioned between the first light source and the projection-pattern element along the projection optical axis.
- The system according to claim 304 308, wherein a major plane of 312. (Currently Amended) the projection-imaging element is oriented substantially perpendicular to the projection optical axis and a major plane of the projection-pattern element is oriented substantially perpendicular to the projection optical axis.

313. (Currently Amended) The system according to claim 304 308, further comprising a second light source that directs substantially unpatterned light onto the device, the second light source being activated in conjunction with the imager to obtain two-dimensional intensity data about the device from the imager.

314-315. (Cancelled)

316. (Currently Amended) The method according to claim 315 318, wherein the projecting substantially unpatterned light source includes a elongated light beam, wherein a longitudinal axis of the beam is perpendicular to the direction of projection and parallel to the grid lines.

317. (Cancelled).

318. (Currently Amended) The method according to claim 317,

A method for measuring a three-dimensional geometry of a device having a surface to be measured, comprising:

projecting patterned light having a spatial-modulation pattern; the projecting pattern light including:

projecting substantially unpatterned light;
spatially modulating the unpatterened light with a sine-wave spatial modulation
pattern to produce spatial-modulation patterned light; and
imaging the spatial-modulation patterned light onto the device;

scanning the device with the spatial-modulation patterned light;

receiving reflected light from the device into at least three linear imager regions,
wherein the spatially modulating includes modulating with a repeating pattern of grid lines
having substantially constant density along lines in a direction parallel to the grid lines and a
sine-wave density along lines in a direction perpendicular to the grid lines; and

projection masking to an elongated aperture having a length axis substantially greater that a width axis, and wherein the length axis is substantially parallel to the grid lines of the pattern

wherein the projection masking limits the projected light to less than about three sine-wave cycles of the sine-wave pattern.

- 319. (Currently Amended) The method according to claim 317 318, further comprising a adjusting a position of the projection masking.
- 320. (Currently Amended) The method according to claim 314 318, further comprising generating a light-intensity control signal based on intensity information regarding the projected light.
- 321. (Currently Amended) The method according to claim 321 318, further comprising controlling a light source to control light output based on the measured light intensity in a feedback manner.
- 322. (Previously Presented) The method according to claim 320, further comprising controlling an imager to control an amount of light received in an imaging cycle of the imager.
- 323. (Currently Amended) The method according to claim 314 318, further comprising condensing light onto the projection-pattern along the projection optical axis.
- 324. (Currently Amended) The method according to claim 314 318, further comprising reflectively focusing to substantially focus an image of the light source adjacent to the light source.
- 325. (Currently Amended) The method according to claim 314 318, wherein the reception optical axis is oriented to be at substantially a right angle to a direction of scanning, and the projection optical axis is oriented to be at substantially a forty-five-degree angle to the direction of scanning.

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A computer-readable medium having computer-executable instructions thereon to 327. (New) cause a suitably configured information-handling system to perform a method comprising:

projecting patterned light having a spatial-modulation pattern; the projecting pattern light including:

> projecting substantially unpatterned light; spatially modulating the unpatterened light with a sine-wave spatial modulation pattern to produce spatial-modulation patterned light; and imaging the spatial-modulation patterned light onto the device;

scanning the device within the spatial-modulation patterned light;

receiving reflected light from the device into at least three linear imager regions, wherein the spatially modulating includes modulating with a repeating pattern of grid lines having substantially constant density along lines in a direction parallel to the grid lines and a sine-wave density along lines in a direction perpendicular to the grid lines; and

projection masking to an elongated aperture having a length axis substantially greater that a width axis, and wherein the length axis is substantially parallel to the grid lines of the pattern wherein the projection masking limits the projected light to less than about three sine-wave cycles of the sine-wave pattern.

- 328. (New) The medium of claim 327, further comprising instructions that cause the method to further include adjusting a position of the projection masking.
- The medium of claim 327, further comprising instructions that cause the method 329. (New) to further include generating a light-intensity control signal based on intensity information regarding the projected light.
- The medium of claim 327, further comprising instructions that cause the method 330. (New) to further include controlling a light source to control light output based on the measured light intensity in a feedback manner.

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331. (New) The medium of claim 327, further comprising instructions that cause the method to further include controlling an imager to control an amount of light received in an imaging cycle of the imager.

332. (New) The medium of claim 327, further comprising instructions that cause the method to further include controlling an imager to control an amount of light received in an imaging cycle of the imager.